

2011 International Conference on Frontiers of Characterization and Metrology for Nanoelectronics



David G. Seiler, Chief
Semiconductor Electronics Division
National Institute of Standards and
Technology

NIST

cea **leti**

MINATEC®

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On behalf of:

- **Committee Co-Chairs:**

- David Seiler, NIST



- Alain Diebold, College of Nanoscale Science and Engineering, SUNY Albany



- Bob McDonald, formerly of Intel (Treasurer)



- Dan Herr, SRC



- George Thompson, Intel



- Amal Chabli, LETI



On behalf of:

- **Committee Members:**

- Alexander Braun, formerly of Semiconductor International



- Michael Current, Frontier Semiconductor



- Dick Hockett, Evans Analytical Group LLC



- Toshihiko Kanayama, AIST



- Rajinder Khosla, NSF



- David Kyser, Applied Materials



- Shifeng Lu, Micron



- **Continued**

- Ulrich Mantz, Zeiss



- Lori S. Nye, Brewer Science, Inc.



- Yaw Obeng, NIST



- Sandip Tiwari, Cornell University



- Victor Vartanian, ISMI



- Wilfried Vandervorst, IMEC



- Ehrenfried Zschech, Fraunhofer IZFP Dresden



Grenoble: a City of History and Science



The Synchrotron ring at the confluence of the Isère and the Drac.



The cable cars to the Bastille.



Grenoble (France), coat of arms. The first records of the three roses dates back to 1279.



Rue and porte de Bonne. Napoleon entered Grenoble through this gateway the night of March 7, 1815 at the beginning of the hundred days.



Fountain of the Three Orders (1897)

2011 FCMN at MINATEC

- First time in series the conference has been outside of the United States
- Very Special Thanks to Our CEA-LETI Hosts!
 - Amal Chabli
 - Didier Molko
 - Michel Brillouet



New Sponsors

- Gold Sponsors

- City of Grenoble



- Grenoble Suburb community



- Rhône-Alpes Region



- Metryx



- CEA-LETI



- National Institute of Standards and Technology



- Silver Sponsors

- Jordan Valley Semiconductor, Ltd.



- Booths

- Cameca



Ground Floor

Elevator

Restrooms

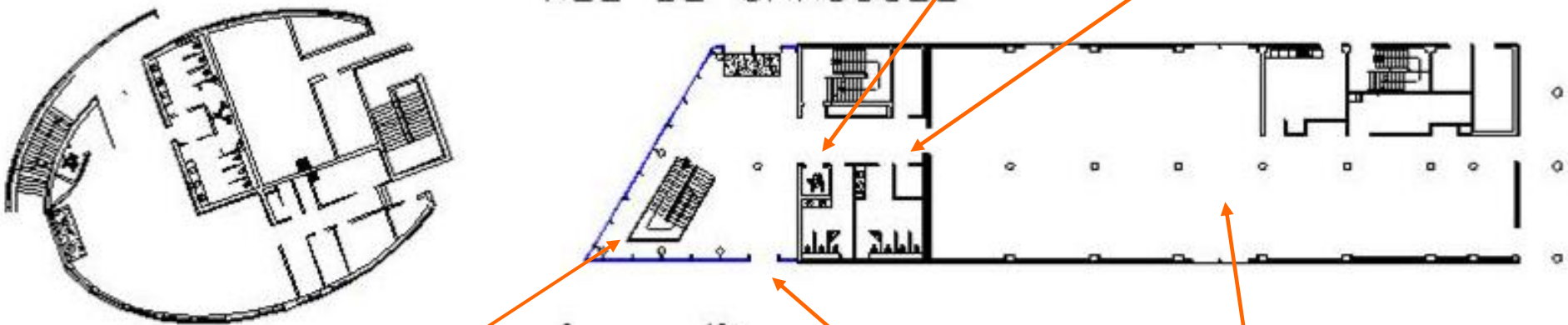
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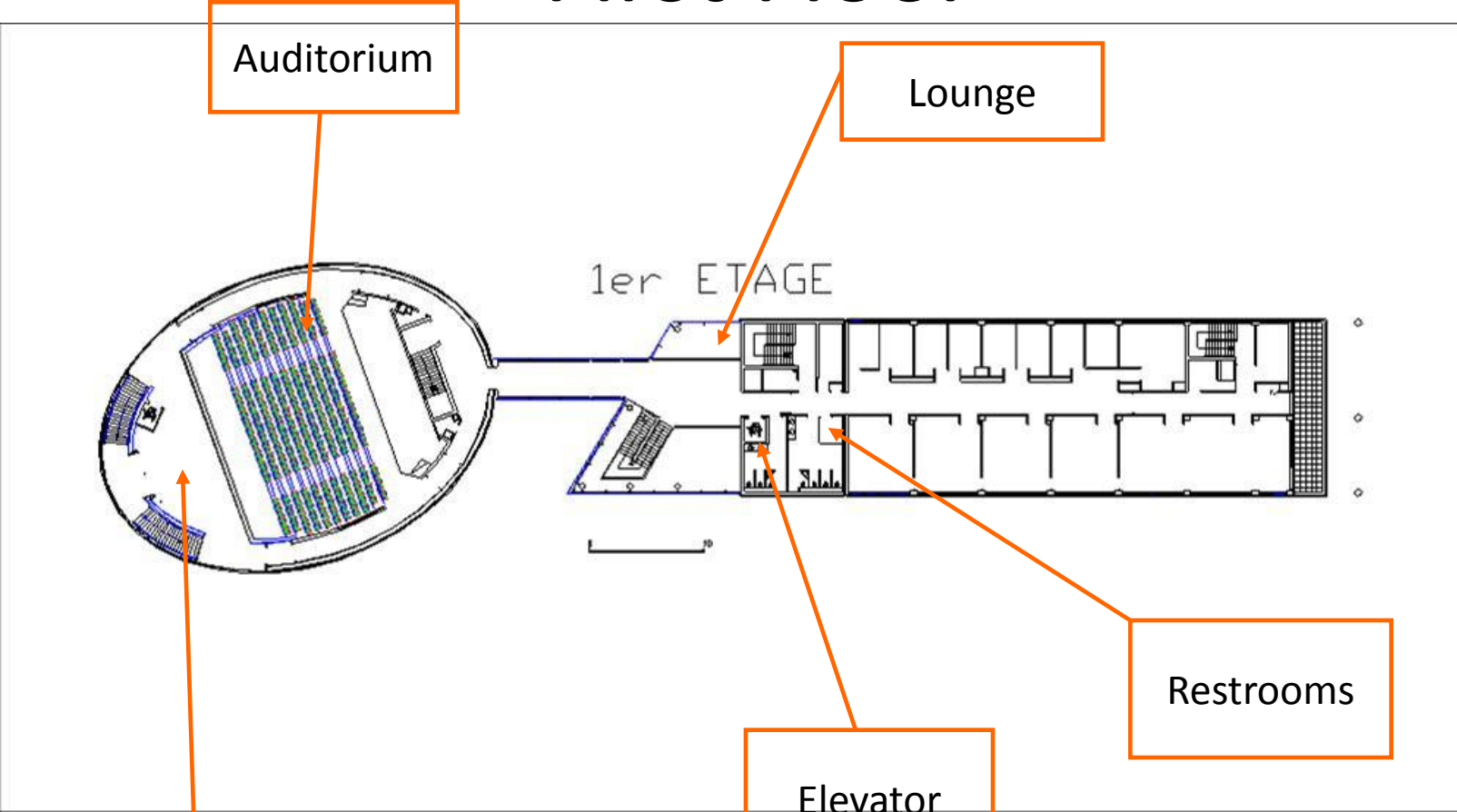
Registration Desk

Maison MINATEC
entrance

Lunch
Coffee Breaks
Posters



First Floor



Auditorium

Lounge

Restrooms

Elevator

Auditorium Control Room



WIFI Access

- WIFI :

ID : 21mmnt11

Password :sfhvELk5

Please note: WIFI and power outlets are available ONLY outside of the auditorium.



Dinner Banquet

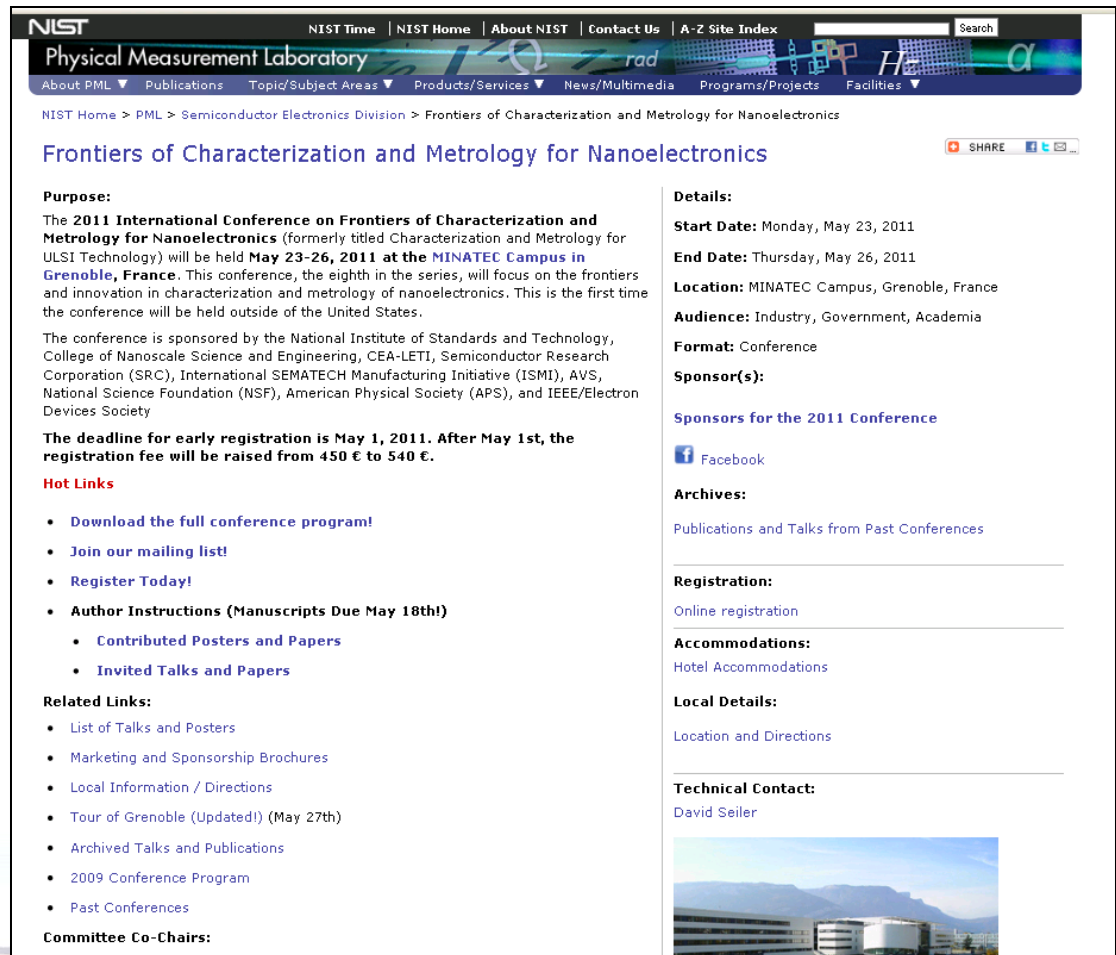
- 6:45 PM on May 25th, by tramway and cable car. Tramway should be taken in front of the entrance of MINATEC
- "restaurant du téléphérique" at the Bastille.
 - A tramway in front of MINATEC will depart at 6:45 PM, followed by a 10 minute walk through the "Jardin de Ville" and then cable car to the restaurant.
 - For additional details, please stop by the registration desk.



Conference Website Success

www.nist.gov/pml/semiconductor/conference/

- From the year 2000 to the present the NIST metrology conference web page has received more than 2.9 million web page views
- The 2009 and 2011 Metrology Frontiers Conferences have accounted for more than 730,000 page views thus far.



The screenshot shows the NIST website for the 2011 International Conference on Frontiers of Characterization and Metrology for Nanoelectronics. The page features a navigation bar with links to NIST Time, NIST Home, About NIST, Contact Us, and A-Z Site Index. The main content area includes a breadcrumb trail, a search bar, and a 'SHARE' button. The conference details are organized into sections: Purpose, Details, Hot Links, Related Links, and Committee Co-Chairs. The Purpose section states that the conference will be held in Grenoble, France, from May 23-26, 2011. The Details section provides information on the start and end dates, location, audience, format, and sponsors. The Hot Links section offers links to download the full conference program, join the mailing list, register today, and access author instructions. The Related Links section includes links to a list of talks and posters, marketing and sponsorship brochures, local information, a tour of Grenoble, archived talks and publications, and past conferences. The Committee Co-Chairs section is also present. A Facebook link and an Archives section are also visible.

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Physical Measurement Laboratory rad He α

About PML Publications Topic/Subject Areas Products/Services News/Multimedia Programs/Projects Facilities

NIST Home > PML > Semiconductor Electronics Division > Frontiers of Characterization and Metrology for Nanoelectronics

Frontiers of Characterization and Metrology for Nanoelectronics

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Purpose:
The **2011 International Conference on Frontiers of Characterization and Metrology for Nanoelectronics** (formerly titled Characterization and Metrology for ULSI Technology) will be held **May 23-26, 2011 at the MINATEC Campus in Grenoble, France**. This conference, the eighth in the series, will focus on the frontiers and innovation in characterization and metrology of nanoelectronics. This is the first time the conference will be held outside of the United States.

The conference is sponsored by the National Institute of Standards and Technology, College of Nanoscale Science and Engineering, CEA-LETI, Semiconductor Research Corporation (SRC), International SEMATECH Manufacturing Initiative (ISMI), AVS, National Science Foundation (NSF), American Physical Society (APS), and IEEE/Electron Devices Society

The deadline for early registration is May 1, 2011. After May 1st, the registration fee will be raised from 450 € to 540 €.

Hot Links

- [Download the full conference program!](#)
- [Join our mailing list!](#)
- [Register Today!](#)
- **Author Instructions (Manuscripts Due May 18th!)**
 - [Contributed Posters and Papers](#)
 - [Invited Talks and Papers](#)

Related Links:

- [List of Talks and Posters](#)
- [Marketing and Sponsorship Brochures](#)
- [Local Information / Directions](#)
- [Tour of Grenoble \(Updated!\) \(May 27th\)](#)
- [Archived Talks and Publications](#)
- [2009 Conference Program](#)
- [Past Conferences](#)

Committee Co-Chairs:

Details:

Start Date: Monday, May 23, 2011

End Date: Thursday, May 26, 2011

Location: MINATEC Campus, Grenoble, France

Audience: Industry, Government, Academia

Format: Conference

Sponsor(s):

Sponsors for the 2011 Conference

Facebook

Archives:

[Publications and Talks from Past Conferences](#)

Registration:

[Online registration](#)

Accommodations:


[Hotel Accommodations](#)

Local Details:

[Location and Directions](#)

Technical Contact:

David Seiler



Publications

- Agreement between AIP and NIST brings increased visibility to the publications in the FCMN Conference Proceedings
 - Free PDF publications now available from all past proceedings (1995-2009)
 - This represents over 15 years of outstanding research and overviews of critical topics collected from world-wide experts in the field of semiconductor characterization and metrology.
 - www.nist.gov/pml/semiconductor/conference/archives.cfm



NIST Physical Measurement Laboratory

Frontiers of Characterization and Metrology for Nanoelectronics: Archived Publications and Talks

Archived Publications

With a very special thanks to the American Institute of Physics (AIP), we are able to provide access to these collected proceedings from the conference series free of charge. This represents over 15 years of outstanding research and overviews of critical topics collected from world-wide experts in the field of semiconductor characterization and metrology.

Please note that the links below are part of the AIP web-space. We have provided the links because they have information that may be of interest to our users. NIST does not necessarily endorse the view expressed or the facts presented on this site. Further, NIST does not endorse any commercial products that may be advertised or available on this site.

Main AIP Conference Proceedings Selection Page

- D. G. Seiler, A. C. Diebold, R. McDonald, C. M. Garner, D. Herr, R. P. Khosla, E. M. Secula, *Frontiers of Characterization and Metrology for Nanoelectronics: 2009*, American Institute of Physics, Melville, NY, Vol. 1173, 398 pp. (30 September 2009)
- D. G. Seiler, A. C. Diebold, R. McDonald, C. M. Garner, D. Herr, R. P. Khosla, E. M. Secula, *Frontiers of Characterization and Metrology for Nanoelectronics: 2007*, American Institute of Physics, Melville, NY, Vol. 931, 603 pp. (30 September 2007)
- D. G. Seiler, A. C. Diebold, R. McDonald, C. Ayre, R. Khosla, S. Zollner, E. M. Secula, *Characterization and Metrology for ULSI Technology: 2005*, American Institute of Physics, Melville, NY, 11747-4502, Vol 788, 667 pp. (28 September 2005)
- D. G. Seiler, A. C. Diebold, T. J. Shaffner, R. McDonald, S. Zollner, R. P. Khosla, E. M. Secula, *Characterization and Metrology for ULSI Technology: 2003*, American Institute of Physics, Melville, NY, Vol 683, 812 pp. (30 September 2003)
- D. G. Seiler, A. C. Diebold, T. J. Shaffner, R. C. McDonald, W. M. Bullis, P. J. Smith, E. M. Secula, *Characterization and Metrology for ULSI Technology: 2000*, American Institute of Physics, Melville, NY, Vol 350, pp. 1-708 (1 February 2001)
- D. G. Seiler, A. C. Diebold, W. M. Bullis, T. J. Shaffner, R. C. McDonald, E. J. Walters, *Characterization and Metrology for ULSI Technology*, American Institute of Physics, Melville, NY, Vol 449 (1 November 1998)
- W. M. Bullis, D. G. Seiler, A. C. Diebold, *Semiconductor Characterization: Present Status and Future Needs*, American Institute of Physics, Woodbury, NY, 729 p. (1995) (Coming Soon!)

Related Links:
Archived Publications and Talks
Past Conferences



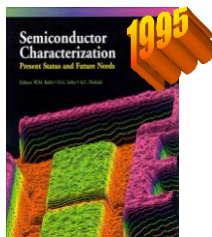
Final Manuscript Deadline

- Tuesday, June 14, 2011
- Author instructions available on-line
www.nist.gov/pml/semiconductor/conference/
- You may be contacted to help review colleagues' manuscripts
- With newly increased visibility, your inclusion in the proceedings is more important than ever!
- See Erik Secula for additional details



NIST Conference Series Provides Focal Point for Frontiers of Semiconductor Metrology

Proceedings Document Metrology Advances



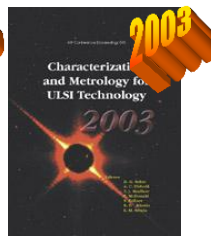
> 280 attendees



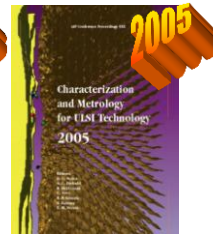
> 295 attendees



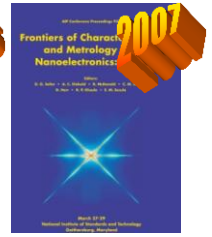
> 235 attendees



> 200 attendees



> 250 attendees



> 230 attendees



> 175 attendees



Some Keynote Speakers



Craig Barrett, formerly President, Intel



Mark Melliar-Smith, formerly President and CEO of SEMATECH



Dennis Buss, VP, Silicon Tech. Development, Texas Instruments



Bob Helms, formerly President and CEO of SEMATECH



Michael Polcari, President and CEO of SEMATECH



Mark Durcan, COO of Micron



Tze-Chiang (T.C.) Chen, IBM Fellow and VP, Science & Technology



Michel Brillouet, Senior Advisor, CEA-LETI

“If you want to meet, greet, and learn from the world’s experts in metrology, this is the place to be.”

Dan Hutcheson, The Chip Insider, January 11, 2007

Please Suggest a Cover Image

We solicit your suggestions for the new book cover. Please send your recommendations to Erik Secula (erik.secula@nist.gov) no later than July 1, 2011.

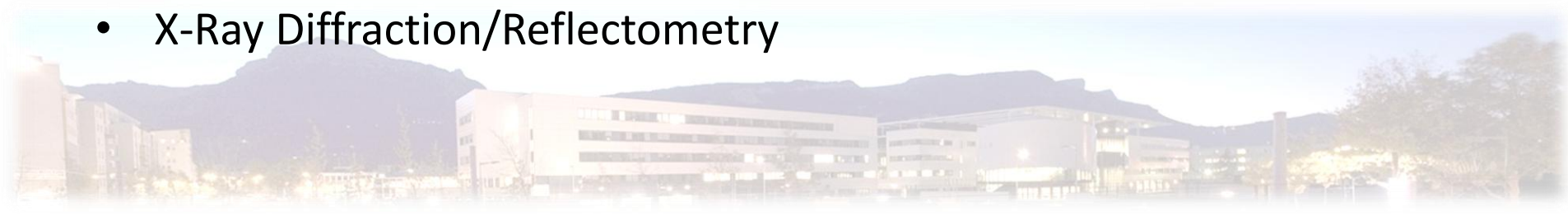
2011

Cover TBD


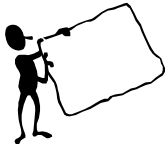



Among the Topics for the 2011 FCMN...

- 3D Integration Metrology
- Atom Probe Tomography
- Atomic Force Microscopy (AFM)
- CD Metrology
- Electron Tomography
- Ellipsometry
- Helium Ion Microscopy
- Scanning Electron Microscopy (SEM)
- Scatterometry
- Time Resolved Cathodoluminescence
- Transmission Electron Microscopy (TEM)
- XPS
- X-Ray Diffraction/Reflectometry



Special Notes

- Talks on-line 
 - Our intention is to put every talk on-line. We will ask the speakers for permission.
- Posters 
 - Posters can be viewed during breaks and during the daily dedicated poster sessions.
 - If you see that some poster numbers are missing, it's because those posters have been withdrawn. Please remember that the poster presenters are expected to put up their posters at the beginning of their presentation day and remove them at the end.
- Silence Cell Phones 



So Let's Begin!

Keynote Talks

Session Chair: David Kyser, Applied Materials

9:00 AM

Nanocharacterization Challenges in a Changing
Microelectronics Landscape

Michel Brillouet, CEA-LETI

9:45 AM

Nanoelectronics and More-than-Moore at IMEC

Marc Heyns, IMEC

